# Paper List

**January – December, 2020**

| E2020-1(F) | Study on CF4/O2 plasma resistance of O-ring elastomer materials  
Tetsuya Goto, Shogo Obara, Tomoya Shimizu, Tsuyoshi Inagaki, Yasuyuki Shirai, and Shigetoshi Sugawa  
[https://doi.org/10.1116/1.5124533](https://doi.org/10.1116/1.5124533) |
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Kaname Imokawa, Takayuki Kurashige, Akira Suwa, Daisuke Nakamura, Taizoh Sadoh, Tetsuya Goto, and Hiroshi Ikenoue  
[http://doi.org/10.1109/JEDS.2019.2956991](http://doi.org/10.1109/JEDS.2019.2956991) |
| E2020-3(C) | An over 120dB dynamic range linear response single exposure CMOS image sensor with two-stage lateral overflow integration trench capacitors  
January 28, 2020, San Francisco, U.S.A  
Yasuyuki Fujihara, Maasa Murata, Shota Nakayama, Rihito Kuroda, Shigetoshi Sugawa  
[https://doi.org/10.2352/ISSN.2470-1173.2020.7.ISS-143](https://doi.org/10.2352/ISSN.2470-1173.2020.7.ISS-143) |
| E2020-4(L) | Amorphous titanium-oxide supercapacitors with high capacitance  
Mikio Fukuhara, Tomoyuki Kuroda, Fumihiko Hasegawa, Yasuyuki Shirai, Tomoyuki Suwa, Toshiyuki Hashida and Masahiko Nishijima  
| E2020-5(F) | Over 100 Million Frames per Second 368 Frames Global Shutter Burst CMOS Image Sensor with Pixel-wise Trench Capacitor Memory Array  
Sensors (MDPI), **Vol.20**, No.4, (2020), pp.16  
Manabu Suzuki, Yuki Sugama, Rihito Kuroda and Shigetoshi Sugawa  
[https://doi.org/10.3390/s20041086](https://doi.org/10.3390/s20041086) |
| E2020-6(F) | High reliability CoFeB/MgO/CoFeB magnetic tunnel junction fabrication using low-damage ion beam etching  
Hyeonwoo Park, Akinobu Teramoto, Jun-ichi Tsuchimoto, Keiichi Hashimoto, Tomoyuki Suwa, Marie Hayashi, Rihito Kuroda, Koji Tsunekawa, and Shigetoshi Sugawa  
[https://doi.org/10.35848/1347-4065/ab6cb5](https://doi.org/10.35848/1347-4065/ab6cb5) |
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E2020-13(W)  CMOS FOR AUTOMOTIVE, MEDICAL, AND INDUSTRIAL APPLICATIONS
Yasuyuki Fujihara

E2020-14(C)  Over 230 fF/μm2 capacitance density 9.0V breakdown voltage textured deep trench SiN capacitors toward 3D integration
Koga Saito, Ayano Yoshida, Rihito Kuroda, Hiroshi Shibata, Taku Shibaguchi, Naoya Kuriyama and Shigetoshi Sugawa

E2020-15(W)  A Study on High Full Well Capacity Wide Dynamic Range Wide Spectral Response CMOS Image Sensor and its Applications
Yasuuki Fujihara, Maasa Murata, Shota Nakayama, Rihito Kuroda, and Shigetoshi Sugawa